

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

Form PTO-1449 (Modified)
(Use several sheets if necessary)

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| Application Number | 09/811,925 |
| Confirmation Number | 1111 |
| Filing Date | March 19, 2001 |
| First Named Inventor | Eric J. BERGMAN |
| Group Art Unit | 1746 |
| Examiner Name | Z. El Arini |
| Attorney Docket No. | 54008.8012.US01 |

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Sheet 1 of 4

U.S. PATENT DOCUMENTS

| Examiner Initials* | Cite No. | U.S. Patent or Application | | Name of Patentee or Inventor of Cited Document | Date of Publication or Filing Date of Cited Document | Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear |
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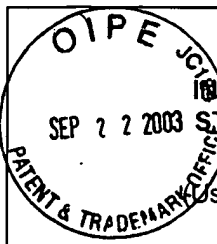
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10/22/03

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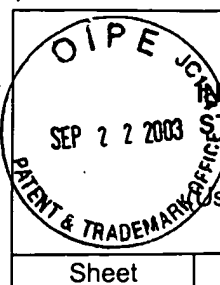
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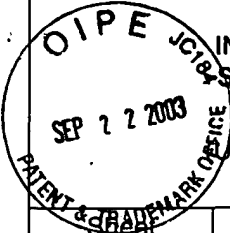
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| ZE | CK | Krusell, W.C. et al., "Cleaning Technology for High Volume Production of Silicon Wafers," <i>ECS Proc. of the First Int'l. Symposium on Cleaning Technology I Semiconductor Device Mfg.</i> , pp. 23-32 (October 1989) | | |
| | CL | Vig, John R., "UV/Ozone Cleaning of Surfaces," <i>U.S. Army Elec. Tech. and Devices Lab.</i> , pp. 1-26 | | |
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| | DN | "Ozone Concentration Measurement In A Process Gas," <i>Proposed IOA Pan American Group Guideline</i> , pp. 1-21 (December 1993) | |
| ZE | DO | "Ozone for Semiconductor Applications," <i>Sorbios</i> , pp. 1-6 (October 1991) | |

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